

IN THE CLAIMS:

Please **CANCEL** claims 23 and 27 without prejudice or disclaimer, and **AMEND** claims 8, 13, 18, 21, 22, and 24, as follows:

1. (PREVIOUSLY AMENDED) An optical apparatus, comprising:
an optical surface;
a thin film having an optical characteristic of wavelength dependence, which is formed on the optical surface; and
a suppressor arranged in an optical path of the optical apparatus to suppress the wavelength dependence in a predetermined wavelength band,
wherein the suppressor has a reflectance characteristic of increasing reflectance on a short wavelength side of a working wavelength region and decreasing reflectance on a long wavelength side of the working wavelength region, and light rays incident on the optical surface include normal incident rays and oblique incident rays .
2. (PREVIOUSLY AMENDED) The optical apparatus according to claim 1, wherein the suppressor is formed on another optical surface different from the optical surface in the optical apparatus.
3. (PREVIOUSLY AMENDED) The optical apparatus according to claim 2, wherein the suppressor is a thin film laid on the other optical surface.
4. (PREVIOUSLY AMENDED) The optical apparatus according to claim 1, wherein the optical characteristic of the thin film is one of reflectance and transmittance.
5. (PREVIOUSLY CANCELLED)
6. (PREVIOUSLY AMENDED) The optical apparatus according to claim 1, wherein the wavelength characteristic of the reflectance of the suppressor has a first region in which the first derivative of the wavelength characteristic is positive on the short wavelength side of the working wavelength region, and a second region in which the second derivative of the wavelength characteristic is negative on the longer wavelength side of the first region.

7. (PREVIOUSLY AMENDED) The optical apparatus according to claim 6, wherein the predetermined wavelength band is defined between the first region and the second region.

8. (CURRENTLY AMENDED) The Optical apparatus according to claim 1, wherein the following relation is satisfied:

$$0.05 \leq \Delta \lambda / \lambda,$$

where λ is a center wavelength of said predetermined wavelength band and $\Delta\lambda$ is a width of said predetermined wavelength band.

9. (PREVIOUSLY AMENDED) An exposure apparatus for transferring a predetermined pattern, formed on a mask under illumination, onto a workpiece, the exposure apparatus comprising the optical apparatus of claim 1.

10. (PREVIOUSLY AMENDED) The exposure apparatus according to claim 9, further comprising a light source for supplying illumination light,

wherein the light source supplies the illumination light including at least two bright lines, and

wherein the at least two bright lines are in the predetermined wavelength band.

11. (PREVIOUSLY AMENDED) The exposure apparatus according to claim 9, further comprising an illumination optical system for illuminating the mask, based on illumination light from a light source, and a projection optical system for forming an image of the pattern of the mask on the workpiece,

wherein the suppressor is provided in at least one of the illumination optical system and the projection optical system.

12. (PREVIOUSLY AMENDED) An exposure method of transferring a predetermined pattern formed on a mask onto a workpiece, using the exposure apparatus of claim 9.

13. (CURRENTLY AMENDED) An exposure apparatus for transferring a predetermined pattern, formed on a mask under illumination, onto a workpiece, comprising:

a light source;

an illumination optical system arranged in an optical path between the light source and the mask;

a projection optical system arranged in an optical path between the mask and the workpiece;

a thin film having an optical characteristic of wavelength dependence, the thin film being formed on an optical surface arranged in at least one of the optical paths; and

a suppressor, arranged in at least one of the optical paths, having a reflectance characteristic of increasing reflectance on a short wavelength side of a working wavelength region and decreasing reflectance on a long wavelength side of the working wavelength region, the suppressor to-suppressing the wavelength dependence in a predetermined wavelength range.

14. (PREVIOUSLY AMENDED) The exposure apparatus according to claim 13, wherein the suppressor is formed on another optical surface different from the optical surface in the at least one of the optical paths.

15. (PREVIOUSLY AMENDED) The exposure apparatus according to claim 14, wherein the suppressor is a thin film laid on the other optical surface.

16. (PREVIOUSLY AMENDED) The exposure apparatus according to claim 15, wherein the optical characteristic of the thin film is one of reflectance and transmittance.

17. (PREVIOUSLY AMENDED) The exposure apparatus according to claim 13, wherein the predetermined wavelength range includes a wavelength of an illumination light.

18. (CURRENTLY AMENDED) An exposure method of transferring a predetermined pattern, formed on a mask under illumination, onto a workpiece, comprising:

providing a light from a light source;

illuminating the mask with the light from the light source;

projecting the pattern on the mask onto the workpiece;

passing the light through a thin film with an optical characteristic having wavelength dependence; and

passing the light through a suppressor,

wherein the thin film is formed on an optical surface in an optical path between the light source and the workpiece, and

wherein the suppressor suppresses the wavelength dependence in a predetermined wavelength range and has a reflectance characteristic of increasing reflectance on a short wavelength side of a working wavelength region and decreasing reflectance on a long wavelength side of the working wavelength region.

19. (PREVIOUSLY AMENDED) The method according to claim 18, wherein the predetermined wavelength range includes a wavelength of an illumination light.

20. (PREVIOUSLY AMENDED) The method according to claim 18, wherein the optical characteristic of the thin film is one of reflectance and transmittance.

21. (CURRENTLY AMENDED) An optical apparatus, comprising:
an curved-optical surface;
a thin film with an optical characteristic having wavelength dependence, the thin film being formed on the curved-optical surface; and
a suppressor arranged in an optical path of the optical apparatus, the suppressor suppressing the wavelength dependence in a predetermined wavelength band and having a reflectance characteristic of increasing reflectance on a short wavelength side of a working wavelength region and decreasing reflectance on a long wavelength side of the working wavelength region.

22. (CURRENTLY AMENDED) The optical apparatus according to claim 21, wherein the suppressor is formed on another optical surface different from the curved-optical surface in the optical apparatus.

23. (CANCELLED)

24. (CURRENTLY AMENDED) The optical apparatus according to claim 2322, wherein the suppressor is a thin film laid on the another optical surface.

25. (PREVIOUSLY ADDED) The optical apparatus according to claim 24, wherein the optical characteristic of the thin film is one of reflectance and transmittance.

26. (PREVIOUSLY ADDED) An exposure apparatus for transferring a predetermined pattern, formed on a mask under illumination, onto a workpiece, comprising the optical apparatus according to claim 21.

27. (CANCELLED)